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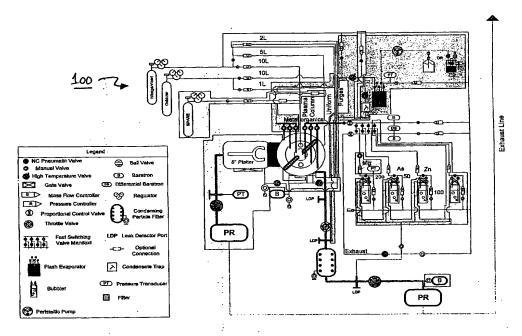
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(54) Title: SYSTEM AND METHOD FOR FORMING MULTI-COMPONENT FILMS



(57) Abstract: A system and a method for depositing films of a multi-component material by MOCVD utilizes a flash evaporator for providing vaporized reactant material at a high flow rate. The high flow rate enables film deposition to occur at a higher deposition rate that what is possible with conventional MOCVD systems. The system may be a single-chamber system or part of a multiplechamber system. The multiple-chamber system allows multi-layer structures to be deposited and/or processed in situ.



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